An Efficient and Chemoselective Deprotection of tert-Butyldimethylsilyl Protected Alcohols Using SnCl₂·2H₂O as Catalyst

Jun HUA, Zhi Yong JIANG, Yan Guang WANG*

Department of Chemistry, Zhejiang University, Hangzhou 310027

Abstract: An efficient and selective method for the deprotection of primary alcoholic *tert*-butyldimethylsilyl (TBS) ethers using SnCl₂·2H₂O as catalyst is described. The reaction conditions allow primary alcoholic TBS ethers to be desilylated chemoselectively in the presence of phenolic TBS ethers, secondary and tertiary alcoholic TBS ethers, and the extensively used TBDPS-, acetyl-, benzyloxycarbonyl-, *p*-toluenesulfonyl- and benzyl protective groups.

Keywords: tert-Butyldimethylsilyl (TBS) ethers, deprotection, tin dichloride.

Protection/deprotection sequences continue to be crucially important in the synthesis of natural products and other complex organic molecules¹. Ever since its discovery by Corey et al.^{1b} in 1972, t-butyldimethylsilyl (TBS) group has become one of the most popular protective groups for hydroxyl groups in organic synthesis because it can be easily installed in high yields and is robust to a variety of reaction conditions. Methods generally used to cleave Si-O bond in TBS ethers for parent alcohol regeneration in clued acid-catalyzed Si-O cleavage with protic acids and Lewis acids such as BF_3^2 , BCl_3^3 , PdCl₂(CH₃CN)₂⁴, BiBr₃⁵, Sc(OTf)₃⁶, InCl₃⁷, cerium(III) chloride heptahydrate/Nal⁸, Zn(BF₄)⁹₂, Ce(OTf)₄¹⁰ and ZnBr₂¹¹, and Lewis base-catalyzed Si-O cleavage employing fluoride ion. Other reagents such as P(MeNCH₂CH₂)₃N, salts of BF₄, organotin reagents, (Me₂N)₃S[F₂SiMe₃] have also been reported to desilvlate TBS ethers of Recently, we have disclosed our works on selective desilvlation of alcohols¹². TBS-protected phenols using CsCO₃/DMF or KOH/EtOH¹³. As a part of our effort to develop highly selective methods for deprotection of TBS ethers, herein we would like to report a procedure for the selective desilvlation of TBS-protected primary alcohols employing SnCl₂·2H₂O as catalyst.

Initially, we used 1 euqiv. of $SnCl_2 \cdot 2H_2O$ to selectively remove the silvl group of TBS-protected alcohols in the presence of phenolic TBS ethers in CH₃CN according to Cort's method¹⁴. However, both yields and chemoselectivities were not satisfactory. Then we investigated the effects of solvents and the amount of $SnCl_2 \cdot 2H_2O$ on the reaction, and found that catalytic amount of $SnCl_2 \cdot 2H_2O$ in EtOH-H₂O is the favored condition for deprotection of primary alcoholic TBS ethers.

^{*} E-mail: orgwyg@zju.edu.cn

Investigation of reaction conditions demonstrated that the reaction could be performed smoothly using 0.5 equiv. of $SnCl_2 \cdot 2H_2O$ in ethanol- H_2O (10:1) at room temperature. We examined a variety of substrates including primary, secondary and tertiary alcoholic TBS ethers. As shown in **Table 1**, only primary alcoholic TBS ethers could be deprotection in excellent yields (**Table 1**, entries 1-4). The cleavage of secondary and tertiary alcoholic TBS ethers was very difficult even in a prolonged reaction time (**Table 1**, entries 5 and 6). The compound with both primary and secondary hydroxyl TBS ethers gave a primary hydroxyl-deprotected product in 83% yield (**Table 1**, entry 7).

	Table 1	Desilylation	of alcoholic	TBS ethers ^a
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Entry	Silyl ethers	Products	Time (h)	Yield (%) ^b
1	<i>n</i> -C ₈ H ₁₇ OTBS	<i>n</i> -C ₈ H ₁₇ OH	2.1	96
2	p-MeOC ₆ H ₄ CH ₂ OTBS	<i>p</i> -MeOC ₆ H ₄ CH ₂ OH	1.5	96
3	C ₆ H ₄ CH ₂ OTBS	C ₆ H ₄ CH ₂ OH	1.9	87
4	p-NO ₂ C ₆ H ₄ CH ₂ OTBS	<i>p</i> -NO ₂ C ₆ H ₄ CH ₂ OH	3.4	90
5	Cyclo-C ₆ H ₁₁ OTBS	Cyclo-C ₆ H ₁₁ OH	12	24
6	t-BuOTBS	t-BuOH	12	Trace
7	TBSO AcO OAc	TBSO AcO OAc	4.0	83

^a All reactions were performed on a 1 mmol scale using 0.5 equiv of $SnCl_2 \cdot 2H_2O$ in 1 mL of EtOH-H₂O (10:1) at room temperature for the time indicated. ^bIsolated yield.

 Table 2
 Selective cleavage of alcoholic TBS ethers^a

Entry	Silyl ethers	Time (h)	Products	Yields (%) ^b
1	p-TBSOC ₆ H ₄ CH ₂ OTBS	1.5	<i>p</i> -TBSOC ₆ H ₄ CH ₂ OH	94
2	p-TBSOC ₆ H ₄ CH ₂ CH ₂ OTBS	1.5	<i>p</i> -TBSOC ₆ H ₄ CH ₂ CH ₂ OH	96
3	p-TBSOC ₆ H ₄ CH=CHCH ₂ OTBS	1.8	<i>p</i> -TBSOC ₆ H ₄ CH=CHCH ₂ OH	87
4	TBDPSO	2.8	TBDPSO	77
5	AcO	2.0	AcO	96
6	CbzOOTBS	1.5	CbzO	91
7	TsOOTBS	2.0	TsOOH	95
8	BnOOTBS	1.5	BnO	93
9	THPO	1.5	THPO	24

^a All reactions were performed on a 1 mmol scale using 0.5 equiv of $SnCl_2 \cdot 2H_2O$ in 1 mL of EtOH-H₂O (10:1) at room temperature for the time indicated. ^bIsolated yield.

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To establish the chemoselectivity of this method, deprotection of the alcoholic TBS ethers bearing phenolic TBS silyl ethers and other sensitive protective groups were studied. The results are summarized in **Table 2**. The alcoholic TBS ethers could be deprotected completely, while TBS-protected phenols (**Table 2**, entries 1-3) as well as TBDPS (**Table 2**, entry 4), acetyl (**Table 2**, entry 5), benzyloxycarbonyl (**Table 2**, entry 6), *p*-toluenesulfonyl (**Table 2**, entry 7) and benzyl (**Table 2**, entry 8) protected alcohols were not touched under the reaction conditions. Tetrahydropyranyl (THP) ether could be partially removed (**Table 2**, entry 9).

In summary, we have developed a facile and efficient procedure for the cleavage of alcoholic TBS ethers using 0.5 equiv. $SnCl_2 \cdot 2H_2O$ in EtOH-H₂O (10:1) at room temperature. The method is specific for deprotection of primary alcoholic TBS ethers. The phenolic TBS ethers, secondary and tertiary alcoholic TBS ethers, and the extensively used TBDPS, acetyl, benzyloxycarbonyl, *p*-toluenesulfonyl and benzyl protective groups remained to be not touched.

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